SRAM supply voltage scaling: a reliability perspective

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Outline

- ♦ Introduction and contributions
- ◊ SRAM cell's failure modeling (90nm CMOS)
- ♦ Leakage-power optimization results (90nm CMOS)
- ◊ Conclusions

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Cache/SRAM trends in microprocessors



Courtesy: Intel, Borkar et al. [2000]

For Intel microprocessors:

- Cache size, cache contribution to the total area, and leakage-power
 percentage in chip increase with technology or year
- ♦ As a result, cache leakage-power is a significant fraction of the total chip power

SRAM leakage in sensor nodes

For "mostly-idle" devices, SRAM leakage dominates

the total power

 $\circ~$ Consider the Charm chip of picoRadio group

designed for sensor nodes

- $\,\circ\,$ SRAM is the largest block with 65% transistors
- During standby, SRAM needs power supply to retain the data, while other blocks are turned off



Figure: The Charm Chip [Sheets-Rabaey et al.]

An obvious method to reduce the leakage-power is to reduce the supply voltage at which the data is stored in standby [Kim-Blauuw et al.'02, Qin-Rabaey et al.'04]
How much voltage reduction is possible?

What stops cache supply voltage reduction?

Example: (Hold failures)

 \diamond An SRAM cell has a minimum supply voltage for preserving data and it is called the data-retention voltage (*DRV*) [Qin-Rabaey, et al.'04]

◊ Due to process-variations, *DRV* exhibits a range of values



Main idea

- Standby mode: SRAM has to store data, but read or write activity is zero
- Standby voltage can be reduced, till
 storage failures happen
- ♦ The min. voltage needed to store all
 - the bits determines the leakage power

SRAM cell failure mechanisms

 $\langle \rangle$

 \Diamond



SRAM cell's channel (probabilistic) model

SRAM cell model:

For a bit U that has been written into the SRAM cell, the following inputoutput probabilistic model will be used,

$U \longrightarrow SRAM \\CELL \\ \downarrow v, t_0 $	$Y \qquad Y =$ $Y =$ $Y =$ $Y =$	× (erasure), with U^c (error), with U^c (error), with U , otherwise U , otherwise U ,	th prob. $p_x(v)$ th prob. $p_e(v)$ herwise
Cause of data-failure	Type of fault	Cause	Probability
Read/Write/Access/Hold	Erasure/spatial	Process variations	$p_x(v)$
Soft-error	Error/Temporal	Radioactivity	$p_e(v) = t_0 r_s(v)$

Main ideas used in this work

Trade-off consists of the following steps:

- ♦ Reduce supply voltage aggressively
- ♦ Allow individual SRAM cells to be (statistically) more prone to failures
- ♦ Use system level techniques error correction coding and data-refresh
 - (scrubbing) to compensate for the increase in per cell "failure"
- Minimize leakage power, including coding overheads, over choice of supply voltage

Related work: Error correction codes in SRAM

- Ostly a parity check or a single-bit error correction code is used in cache for extra reliability [Spica-Mak'04, Slayman'05]
- [Heegard-El Gamal'83] studied capacity of memories; [Slayman'05] summarizes error-correction codes aspects of SRAM, etc.

Related work: data-refresh (or scrubbing)



Trade-offs while scrubbing:

- ◊ Mitigates bit-error accumulation due to soft-errors (or any other noise mechanism)
- Onsumes extra power, which has to be accounted for, while reducing leakage

Research literature:

- ◊ Proposed for increasing reliability of memory/storage systems [Saleh et al.'90]
- ◊ Error probability improvement due to scrubbing have been calculated for selected error correction codes in the presence of soft-errors by [Bajura et al.'07]

Proposed low-leakage SRAM block diagram



 $(B_1, ..., B_k)$ is the data-bit vector to be stored

 \Diamond Input is encoded by a rate k/n, n > k code to $(U_1, ..., U_n)$

 \Diamond After each refresh time-period, $(Y_1, ..., Y_n)$ is decoded to $(\widehat{B}_1, ..., \widehat{B}_k)$ and restored

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Contributions and performance metrics

- Trade-offs between leakage-power, error-correction code, error probability and data-refresh rate are presented using circuit level simulations (90nm CMOS) – principal "knob" being the supply-voltage
- Efficient statistical estimation method to obtain the circuit-level probabilistic model of SRAM cell is developed

Cost and constraint functions

Cost:
$$\mathscr{P}_b := \mathscr{P}_b(v, t_r, ECC) = \frac{n}{k} P_l(v) + \frac{\text{refresh energy}}{kt_r}$$

where $P_l(v)$ is the leakage power at voltage v

Constraint: Given *ECC*, choose t_r such that error probability at v is equal to error probability at v = 1.0V with [31, 26, 3] Hamming code

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Optimization framework

Within the cost-constraint setup from the previous slide, the following separable optimization framework is developed [Kumar-Rabaey-Ramchandran'09], [Kumar(Thesis)'08]



Circuit techniques to reduce leakage power

- Circuit level technique have also been proposed to reduce the leakage power
 - Modification of SRAM cell's transistor parameters, e.g., [Zhao et al.'04, Qin-Rabaey et al.'08]
 - Addition of sleep transistors or control gate, e.g., [Zhang et al.'05, Agarwal-Roy'03]
 - Designing an asymmetric SRAM cell, e.g., [Azizi et al.'03]
 - Usage of new transistors like FINFET, e.g., [Guo-King-Nikolic et al.'05]
 - Using a different structure than 6-Transistor SRAM cells, e.g., [Calhoun-Chandrakasan'06, Ali-Faisal-Bayoumi'05]
- These techniques are "stackable" with the technique proposed in this talk

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Simplifying assumptions

- The failures are spatially independent
 - Achieved by interleaving at a negligible energy cost (distributes MBU) [Slayman'05, Blum et al.'07]
 - The parametric failures are spatially fixed, and hence they are determined as erasures or don't care (x) by test-patterns
 - Soft-errors are spatially/temporally random
- Soft-errors don't happen during read/write (negligible probability)



SRAM channel model's constituents

- At v = 0.2V, the SRAM cell was not writeable. The supply voltage range to consider is 0.3V to 1.0V
- ♦ The parametric failure probability is the erasure probability

$$p_x(v) = p_{pf}(v) \le p_r(v) + p_w(v) + p_h(v) + p_{at}(v) + p_{wt}(v)$$

 Soft-errors , and other noise-like failures have rates, which determine the error probability

$$p_e(v) \le t_r r_s(v), \qquad p_e(v) << 1$$

Modeling of failures

- ♦ Why modeling?
 - Brute force Monte Carlo simulations will require more than trillion trials
 - ♦ Due to these complexity reasons, supply voltage is chosen in 100mV steps
- ♦ Soft-errors:
 - Estimation with macro-models developed by Freeman'96
- Parametric failure probabilities:
 - Read upset estimation with read-noise margin (RNM)
 - Write failure estimation with write-noise margin (WNM)
 - Access-time failure estimation with extreme value theory
 - Write-time failure estimation with extreme value theory
 - Hold failure negligible compared to read upset

Roy et al.'06 Nassif-Agarwal'07 Meindl et al.'01 Bhavnagarwala'05 Kumar-Rabaey-Ramchandran'09

Soft-error rate estimation



Critical charge: Minimum charge q_C needed in the radiation induced current-pulse for flipping the SRAMstate

- [Freeman'96] [Hazucha'00]

$$r_s(v) = K \exp(-\alpha q_C(v))$$

lpha and K are obtained from the literature

Critical charge variation



 Q_c (a.u.) cumulative distribution obtained for the 90nm CMOS tech

 $E[R_s(v)] = E[K \exp(-\alpha Q_C(v))]$

The relative difference

 $(E[R_s] - r_s)/r_s$

due to process variations is negligible

(2-5%) for *v* in [0.3, 1.0]

[Kumar(Thesis)'08, Kumar-Rabaey-Ramchandran'09]

V	0.3	0.4	0.5	0.6	0.7	0.8	0.9	1
$\log_{10}\left(r_{s}(v)\right)$	-15.27	-15.29	-15.31	-15.34	-15.38	-15.43	-15.48	-15.54

Soft-error rate at v = 0.3V is about 1.9 times of Soft-error rate at v = 1.0V

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Parametric failures => read upset



- ♦ Read (static) noise margin is defined as $RNM = min(s_1, s_2)$
- ♦ By convention, if S_1 or S_2 is absent, RNM < 0
- ♦ $RNM \le 0$ indicates a read-upset event
- ♦ It has been observed that $RNM \sim N(\mu_r, \sigma_r^2)$ [Nassif-Agarwal'06]

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Parametric failures => $p_r(v)$



Read noise margin: Observed RNM (normalized) statistics (mean/var) as a function of supply voltage are illustrated. Read upset probability is given by,

$$p_r(v) = Q\left(\frac{\mu_r(v)}{\sigma_r(v)}\right)$$

supply voltage [Kumar(Thesis)'08, Kumar-Rabaey-Ramchandran'09] 0.3 0.4 0.5 0.6 0.7 0.8 0.9 1 V $\log_{10}\left(p_r(v)\right)$ -7.0 -12.3 -27.3 -45.8 -62.7 -72.9 -78.7 -78.9

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Parametric failures => write failure



- Write noise margin is defined as $WNM = \min(s_1, s_2)$
- $WNM \le 0$ indicates a write-failure event
- ♦ Distribution of *WNM* is more complicated to estimate

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Parametric failures => *WNM* **distributions**



- WNM distribution is Gaussian at high-voltages
- Distribution head is estimated by exponential fit to the CDF $F_w(v)$

V	0.3	0.4	0.5	0.6	0.7	0.8	0.9	1
$\log_{10}\left(p_{w}(v)\right)$	-5.72	-6.20	-6.56	-11.09	•••	• • •	•••	• • •

[Kumar(Thesis)'08, Kumar-Rabaey-Ramchandran'09]

Parametric failures => write-time failures



 \diamond If T_{wl} is not large enough, then bit will not be written in successfully \diamond Due to process-variations, T_{wl} exhibits a distribution \diamond <u>Need a method</u> to estimate this distribution's tail

CDF tail: extreme value theory

Use some results from Extreme Value Theory [Balkema-De Haan'74]

$$R_t(x) = P(X > x + t \mid X > t)$$

=> $R_t(x) P(X > t) = P(X > x + t)$

Result: If $R_t(x)$ converges for large *t*, then the limit is exponential

Remarks:

- \diamond Observe that exponential distributions satisfy this property for all t > 0
- It is hard to determine where the tail begins, and whether the distribution decay will change its behavior
- ♦ This technique is a good thumb-rule, in the absence of huge number of trials

Write-time estimation

From 2000 Monte Carlo trials, the 90% point (quantile) is chosen as *t*The residual probability function is plotted to check exponential behavior, if any
Extrapolation used if exponential behavior is found

Remark: For all voltages, the exponential nature of decay was observed



Write-time model

Using extreme value theory, the final write-time model is as follows:

$$P(T_{wl} > x + t) = P(T_{wl} > t) \exp(-\alpha_w x)$$

$$t: P(T_{wt} > t) = 0.1 \qquad [Kumar(Thesis)'08]$$

Using 2000 Monte Carlo trials, *t* and α_w were estimated as follows



Access-time model

Similar to write-time, the following access-time model can be obtained:

$$P(T_{at} > x + t) = P(T_{at} > t) \exp(-\alpha_{at} x)$$

$$t: P(T_{at} > t) = 0.1 \quad [Kumar(Thesis)'08]$$



Failure modeling summary

Soft-errors:

- \diamond Decreases exponentially with critical charge
- Oritical charge evaluated using "noise"-current injection
- Onte-Carlo simulations to compute effect of process-variations

Parametric failures:

◊ Noise margin violations – Read, write, hold

◊ Timing violations – write-time, access

Stimated by Monte-Carlo and distribution-tail predictions

Supply noise:

 \diamond Tackled by 100mV margin

All failure probabilities combined



Observations

- At high voltages, soft-errors dominate the error probability
- At low voltages, parametric failures (notably write failures) take over
- At 0.2V, the SRAM cells were not writeable [Kumar(Thesis)'08]

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Leakage power dependence on supply



This leakage power is obtained by averaging over 1000 trials, using Monte
 Carlo simulations

♦ The faded lines mark the (+/- 1σ) limits

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Cost function and coding families

Cost function with [n, k, d] code :

$$\mathscr{P}_b(v, t_r, ECC) = \frac{n}{k} P_l(v) + \frac{n}{k} \frac{4E_r + 3E_w + E_{ECC}}{t_r}$$

Target error-probability:

 $n = 31, k = 26, d = 3; v = 1.0V, t_0 = data-lifetime, sets$

$$p_{target} = \binom{31}{2} (t_0 \cdot r_s(1.0))^2 = 1.40 \times 10^{-25} (t_0)^2$$

Coding families:

- \diamond Hamming : $d = 3, (n, k) = \{(31, 26), (63, 57), \dots, (511, 502)\}$
- \Diamond BCH codes : $d = 5, 7, ..., 15; n = \{63, 127, ..., 1023\}$

0 < 1024 for approx. spatial statistical independence in 256 by 256 SRAM blocks

Decoding error events

- ♦ For [n, k, d] bounded distance decoding codes
- Generalized decoding error event: x errors and y erasures with
 probabilities p_e(v) and p_x(v), respectively, have the following error
 event [Forney'66, Lin-Costello'83]

$$2x + y > d - 1$$

♦ **Specialized decoding error event:** *z* errors with probability

 $p_e(v) + p_x(v)$ has the following error event

$$2z > d - 1$$

Effect of data-refresh (scrubbing)

Fix code to [31, 26, 3] Hamming code, and $t_0 = 1$ sec

Choose (t_r, v) pairs to meet error-probability target



◊ Leakage power reduction with data-refresh is limited by parametric-failures

Leakage power and ECC trade-offs

For each ECC, Choose (t_r, v) pairs to meet the error-probability target

Find the optimum of cost function for each min. distance among ECC families



m = number of errors that can be corrected

◊ Accounting for parametric failures as erasures leads to better power reduction

 \diamond The upper bound is 94% and 91% reduction is achieved by [127, 106, 7] BCH code

[Kumar(Thesis)'08, Kumar-Rabaey-Ramchandran'09]

Similar trade-offs for 65nm tech.

The same error-probability estimation and algebraic optimization routine can be run in sequence to obtain results for CMOS 65nm (low-leakage) technology



Full set of comparisons can be found in my thesis [Kumar(Thesis)'08]

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- \diamond Refresh and error-correction prevent reliability degradation in SRAM bits with voltage scaling. The leakage power reduction estimates are around 91% for [127, 106, 7] BCH code, and 61% for Hamming codes with n < 512
- ♦ Refresh (scrubbing) can also be used for <u>improving reliability</u> at fixed power
- Sieving spatially random soft-errors and spatially fixed parametric errors leads to possible leakage power reduction with lower complexity codes

Standby SRAM remarks

- In the special case of standby storage (for sensors), read and write based parametric failures can be ignored, thereby resulting in standby leakage-power optimization
- Using this approach, experimental chips were fabricated and tested in the 90nm
 CMOS technology by Huifang Qin (courtesy STMicroelectronics)

Related work on standby SRAM:

- *"Fundamental data retention limits in SRAM standby Experimental results,"* A. Kumar,
 H. Qin, P. Ishwar, J. Rabaey, and K. Ramchandran, ISQED, San Jose, CA, USA, Mar 2008.
- *"Error-Tolerant SRAM Design for Ultra-Low Power Standby Operation,"* H. Qin, A. Kumar,
 P. Ishwar, J. Rabaey, and K. Ramchandran, ISQED, San Jose, CA, USA, Mar 2008.
- 3. *"Fundamental redundancy versus power trade-off in standby SRAM,"* **A. Kumar,** H. Qin, P. Ishwar, J. Rabaey, and K. Ramchandran, ICASSP 2007, Honolulu, Hawaii, USA, Apr 2007.

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